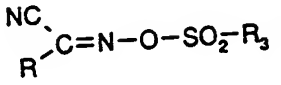
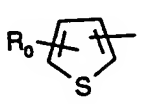
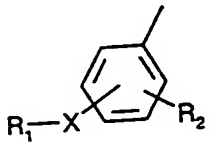
Abstract of the Disclosure

The invention describes the use of oxime alkyl sulfonate compounds of formula 1



(1), wherein

R is naphthyl,  or  ;

R_0 is either an R_1-X group or R_2;

X is a direct bond, an oxygen atom or a sulfur atom;

R_1 is hydrogen, C_1-C_4alkyl or a phenyl group which is unsubstituted or substituted by a substituent selected from the group consisting of chloro, bromo, C_1-C_4alkyl and C_1-C_4-alkyloxy;

R_2 is hydrogen or C_1-C_4alkyl; and

R_3 is straight-chain or branched C_1-C_{12}alkyl which is unsubstituted or substituted by one or more than one halogen atom;

as photosensitive acid generator in a chemically amplified photoresist which is developable in alkaline medium and which is sensitive to radiation at a wavelength of 340 to 390 nanometers and correspondingly composed positive and negative photoresists for the above-mentioned wavelength range.